

**Amendments to the Specification:**

Please amend paragraph [0027] on page 13 as follows:

[0027] An alternate or additional implementation in a method of forming a capacitor in accordance with an aspect of the invention is described with reference to Figs. 5-7. Referring initially to Fig. 5, a substrate fragment 30 comprises a semiconductor substrate 32. A first capacitor electrode 34 is formed over semiconductor substrate 32. Such comprises an exposed metal surface 36, for example as described and having the attributes of inner surface 22 of the above first exemplary embodiment. In one preferred embodiment, first capacitor electrode 34 consists essentially of metal. However, composites of conductive and semiconductive materials are contemplated as long as least some portion of surface 36 comprises an exposed metal surface. Exemplary preferred materials for first capacitor electrode 34 are as otherwise described above with respect to the first described embodiment first capacitor electrode 14.